Amendments to the Claims

This listing of claims will replace all prior versions, and listings, of claims in the application:

Listing of Claims:

- 1. (currently amended)A method of treating a subterranean formation comprising the steps of:
 - (a) providing an aqueous suspension of dispersed particles, wherein the dispersed particles consist essentially of colloidal particles comprising a material selected from the group consisting of silica, aluminum oxide, antimony oxide, tin oxide, cerium oxide, yttrium oxide and zirconium oxide, with the proviso that the colloidal particles are not mica-particulates;
 - (b) injecting down a well an aqueous fluid comprising a thickening amount of a viscoelastic surfactant; and,
 - (c) injecting down a well the aqueous suspension of dispersed particles.

wherein the permeability of said subterranean formation is between about 5 and about 100 md.

- 2. (canceled)
- 3. (currently amended) The method of claim 21, wherein the permeability of said subterranean formation is between about 10 and about 50 md.
- 4. (canceled)
- 5. (original) The method of claim 1, wherein the particles are spherical.
- 6. (original)The method of claim 5, wherein the particles have a diameter ranging from about 8nm to about 250nm.
- 7. (original)The method of claim 1, wherein the particles are elongated.
- 8. (original)The method of claim 7, wherein the particles have a length between about 100 and about 300nm.

9. (original)The method of claim 1, wherein said viscoelastic surfactant is an anionic

surfactant.

10. (original)The method of claim 1, wherein said viscoelastic surfactant is a cationic

surfactant.

11. (original)The method of claim 1, wherein said viscoelastic surfactant is a zwitterionic

surfactant.

12. (previously presented)A method of treating a subterranean formation comprising the

steps of:

(a) providing an aqueous suspension of dispersed particles, wherein the dispersed

particles consist essentially of colloidal particles comprising a material selected from

the group consisting of silica, aluminum oxide, antimony oxide, tin oxide, cerium

oxide, yttrium oxide and zirconium oxide, with the proviso that the colloidal particles

are not mica particulates; and

(b) injecting down a well an aqueous fluid comprising a viscoelastic surfactant and a

hydrophobically-modified polymer, said hydrophobically-modified polymer being

present at a concentration between approximately its overlap concentration c* and

approximately its entanglement concentration ce; and,

(c) injecting down a well the aqueous suspension of dispersed particles.

13. (original)The method of claim 12, wherein the permeability of said subterranean

formation is between about 5 and about 100 md.

14. (original)The method of claim 13, wherein the permeability of said subterranean

formation is between about 10 and about 50 md.

15. (canceled)

16. (original) The method of claim 12, wherein the particles are spherical.

17. (currently amended) The method of claim 16, wherein the particles have a diameter

ranging from about 8nm to about 250nm.

18. (original) The method of claim 12, wherein the particles are elongated.

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19. (original)The method of claim 18, wherein the particles have a length between about 100 and about 300nm.

- 20. (previously presented) The method of claim 12, wherein said viscoelastic surfactant is an anionic surfactant.
- 21. (original)The method of claim 12, wherein said viscoelastic surfactant is a cationic surfactant.
- 22. (previously presented)The method of claim 12, wherein said viscoelastic surfactant is a zwitterionic surfactant.
- 23. (previously presented)The method of claim 1 wherein the colloidal particles are added at a concentration between about 0.1 and 0.5 wt%.
- 24. (previously presented)The method of claim 12 wherein the colloidal particles are added at a concentration between about 0.1 and 0.5 wt%.
- 25. (previously presented) The method of claim 1 wherein the dispersed particles consisting essentially of colloidal particles consist of colloidal particles.